| Ref # | Hits | Search Query | DBs | Default Operator | Plurals | Time Stamp |
|----------|------|----------------------------------------------------------|---------------------------------------------------------|---------------------|---------|------------------|
| L1 | 148 | liang near mong-song.in. | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/06/07 17:36 |
| L2 | 7 | 1 and (low near dielectric) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/06/07 17:37 |
| L3 | 47 | lu near yung-cheng.in. | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/06/07 17:37 |
| L4. | 39 | 3 and (low near dielectric) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/06/07 17:39 |
| L5 | 0 | chang near huilin.in. | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/06/07 17:40 |
| L6 | 2935 | 438/624.ccls. | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR. | ON | 2005/06/07 17:41 |
| L7 | 546 | (low near dielectric) near45 (treatment) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/06/07 17:41 |
| L8 | 522 | (low near dielectric) near25 (treatment) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/06/07 17:42 |
| L9 | 22 | (low near dielectric) near25 (second near5 treatment) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/06/07 17:42 |

| | | | | | | 2007/20/27 17 17 |
|-----|-------|---------------------------------------------------------|---------------------------------------------------------|----|------|------------------|
| Ļ10 | 8 | 9 and stability | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/06/07 17:45 |
| L11 | 112 | 7 and stability | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/06/07 17:52 |
| L12 | 8 | 7 and (mechanical near stability) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/06/07 17:46 |
| L13 | 19 | 7 and (temperature near25 stability) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/06/07 18:03 |
| L14 | 81315 | (second near5 treat\$4) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/06/07 18:03 |
| L15 | 38282 | (second near2 treat\$4) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON . | 2005/06/07 18:03 |
| L16 | 17576 | (second near treat\$4) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/06/07 18:04 |
| L17 | 2 | (second near treat\$4) near15 (low near dielectric) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/06/07 18:04 |
| L18 | 18 | (second near3 treat\$4) near25 (low near dielectric) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/06/07 18:16 |
| L19 | 420 | (hydrogen near3 plasma) near15 (microwave) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/06/07 18:18 |

| L20 | 3 | (hydrogen near3 plasma) near15 (microwave) near15 (electron near beam) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/06/07 18:17 |
|-----|----|---------------------------------------------------------------------------------------|---------------------------------------------------------|------|-----|------------------|
| L21 | 24 | (hydrogen near3 plasma) near15 (microwave) near25 (treatments) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR . | ON | 2005/06/07 18:18 |
| L22 | 24 | (hydrogen near3 plasma) near15 (microwave) near15 (treatments) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON. | 2005/06/07 18:23 |
| L23 | 6 | (hydrogen near3 plasma) near15 (electron near beam) near15 (treatments) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/06/07 18:41 |
| L24 | 6 | (hydrogen near3 plasma) near15 (ultraviolet near radiation) near15 (treatments) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR . | ON | 2005/06/07 18:32 |
| L25 | 10 | (high near temperature) near15 (ultraviolet near radiation) near15 (treatments) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/06/07 18:33 |
| L26 | 0 | (carbon near3 plasma) near15 (electron near beam) near15 (treatments) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/06/07 18:40 |
| L27 | 4 | (carbon near3 plasma) near15 (high near temperature) near15 (treatments) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/06/07 18:40 |
| L28 | 16 | (hydrogen near3 plasma) near15 (high near temperature) near15 (treatments) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/06/07 18:45 |
| L29 | 2 | (first near3 treatment) near15 (pores) near15 (low near dielectric) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/06/07 18:47 |

| L30 | .4 | (second near3 treatment) near15 (pores) near15 (low near dielectric) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/06/07 18:59 |
|-----|-------|----------------------------------------------------------------------------------------------|---------------------------------------------------------|------|----|------------------|
| L31 | 49215 | (first near3 treatment) (hydrogen near2 plasma) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/06/07 19:00 |
| L32 | 1669 | ((first near3 treatment) (hydrogen near2 plasma)) near10 (low ear4 dielectric) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/06/07 19:00 |
| L33 | 102 | ((first near3 treatment) (hydrogen near2 plasma)) near10 (low near4 dielectric) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/06/07 19:00 |
| L34 | 52 | ((first near3 treatment) (hydrogen near2 plasma)) near10 (low near dielectric) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/06/07 19:01 |
| L35 | 0 | ((first near3 treatment) near15 (hydrogen near2 plasma)) near10 (low near dielectric) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/06/07 19:01 |
| L36 | 0 | ((first near3 treatment) near15 (hydrogen near2 plasma)) near10 (low3 near dielectric) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/06/07 19:06 |
| L37 | 0 | ((treatment) near15 (hydrogen near2 plasma)) near10 (low3 near dielectric) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/06/07 19:01 |
| L38 | 21 | ((treatment) near15 (hydrogen near2 plasma)) near10 (low near dielectric) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR . | ON | 2005/06/07 19:01 |
| L39 | 20 | ((treatment) near5 (hydrogen near2 plasma)) near10 (low near dielectric) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/06/07 19:02 |

| L40 | 0 | ((treatment) near5 (microwave near5 hydrogen near2 plasma)) near10 (low near dielectric) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/06/07 19:02 |
|-----|----|----------------------------------------------------------------------------------------------------------------------------------|---------------------------------------------------------|----|----|------------------|
| L41 | 0 | ((first near3 treatment) near15 (high near temperature)) near10 (low3 near dielectric) US-PGPUB USPAT; EPO; JPO; DERWENT IBM_TDB | | OR | ON | 2005/06/07 19:06 |
| L42 | 0 | ((first near3 treatment) near15 (high near temperature)) near10 (low near dielectric) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/06/07 19:06 |
| L43 | 0 | ((first near3 treatment) near25 (high near temperature)) near10 (low near dielectric) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/06/07 19:06 |
| L44 | 35 | ((treatment) near25 (high near temperature)) near10 (low near dielectric) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/06/07 19:07 |
| L45 | 31 | ((treatment) near5 (high near temperature)) near10 (low near dielectric) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/06/07 19:10 |
| L46 | 0 | ((second near treatment) near5 (high near temperature)) near10 (low near dielectric) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/06/07 19:10 |

| | U | 1 | Document ID | Title |
|---|---|---|----------------------|-------------------------------------------------------------------------------|
| 1 | | | US 20040234779 A1 | Fluorinated aromatic precursors |
| 2 | | | US 20030181537 A1 | Process for producing dielectric layers by using multifunctional carbosilanes |
| 3 | | | US 20030157311 A1 | Mesoporous films having reduced dielectric constants |
| 4 | | l | US 20020132061 A1 | Method for producing a porous coating |
| 5 | | | US 6818289 B2 | Mesoporous films having reduced dielectric constants |

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|---|------------|-------|------------|----------------------------------------------------------------------------------------------------------------|
| 6 | 428/447 | 28 | 20031216 | 257/E21.259; 257/E21.26; 257/E21.261; 257/E21.264; 427/489; 427/515; 428/450 |
| 7 | 428/304.4 | 18 | 20030715 | 106/14.13; 106/14.41; 257/E21.273; 427/255.11; 427/372.2; 427/376.2; 427/419.2; 428/312.2 |
| 8 | 118/724 | 37 | 20000711 | 118/715; 118/723ER; 118/723MR; 118/726; 257/E21.259 |